



Park XE15

Power and versatility, brilliantly combined.

Park XE15

Increase your productivity with our powerfully versatile atomic force microscope

The Park XE15 includes many unique capabilities that make it ideal for shared labs that handle a diverse range of samples, researchers doing multi variant experiments, and failure analysis engineers working on wafers. Its reasonable price and robust feature set also make it one of the best value large-sample AFMs in the industry.

Unique MultiSample™ scan boosts research productivity

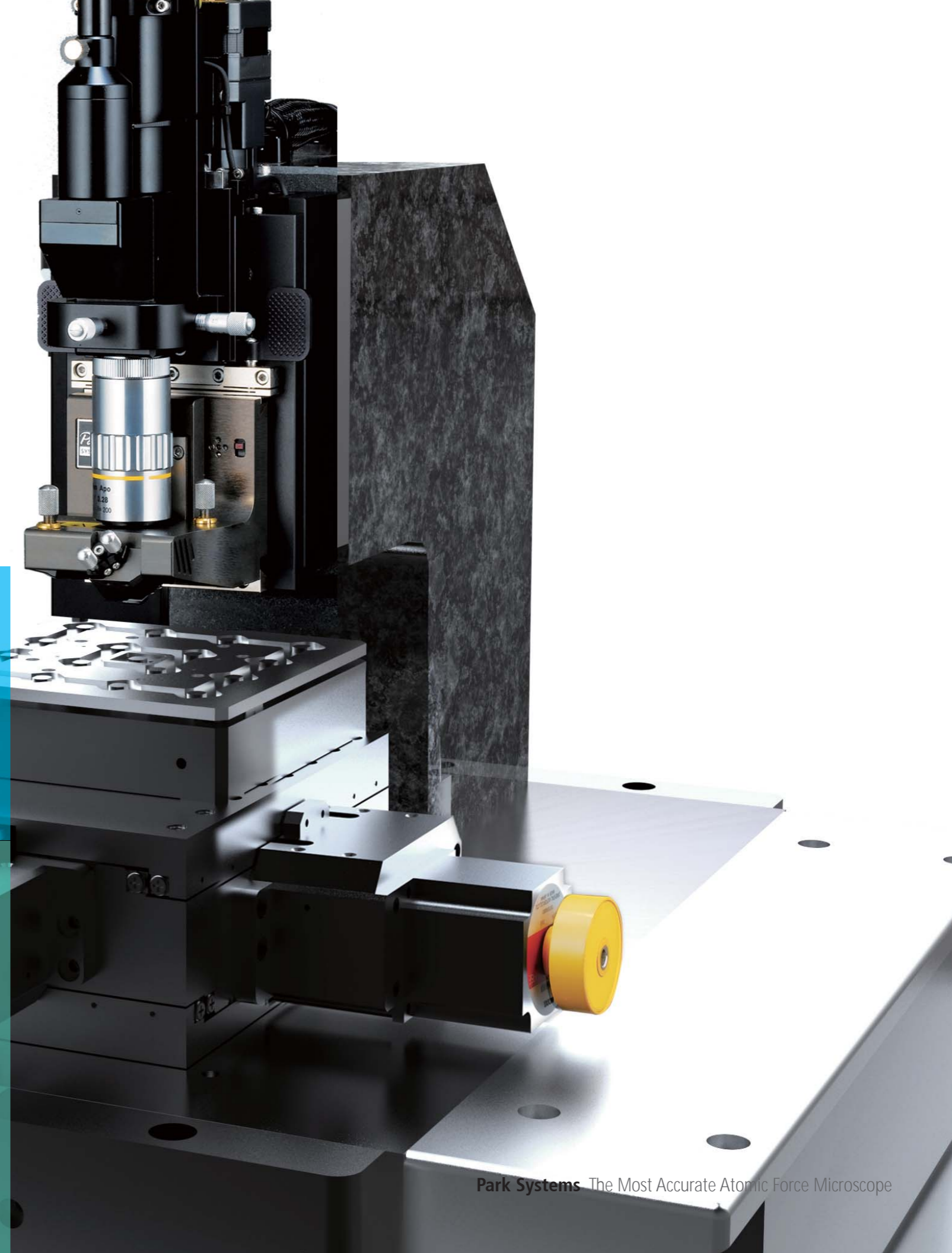
Maximize your efficiency with the only AFM that offers the ability to image and measure multiple samples in one pass. Simply load the stage with your samples and initiate the scan process. This feature also allows you to scan the samples under identical environmental conditions, improving the accuracy and reliability of your data.

Large sample size increases possibilities

Unlike most AFMs, the Park XE15 can scan a sample of up to 150 mm x 150 mm. This makes it ideal for researchers wanting to scan larger samples or failure analysis engineers who need to place silicon wafers on the stage.

Features adaptable to any need

The Park XE15 features our most inclusive set of scan modes and can process a range of sample sizes. This makes it uniquely suited to shared labs with a wide range of individual requirements.





Park XE15

All the features that make Park AFMs the world's most accurate and powerful

The most convenient sample measurements with MultiSample™ scan

- Automated imaging of multiple samples in one pass
- Specially designed multi-sample chuck for the loading of up to 16 individual samples
- Fully motorized XY sample stage travels up to 150 mm x 150 mm.

More accurate scans with Crosstalk Elimination

- Dual independent, closed-loop XY and Z flexure scanners for sample probe and tip
- Flat and linear XY scan of up to 100 μm x 100 μm with low residual bow
- Out of plane motion of less than 2 nm over entire scan range
- Up to 25 μm Z-scan by high force scanner
- More accurate height measurements

Better tip life, sample preservation, and accuracy with True Non-Contact™ Mode

- 10 times larger Z-scan bandwidth than a piezotube based system
- Non contact means less tip wear and longer tip life
- Higher resolution imaging than competing AFMs
- Decreased sample interference for more accurate scans

The most user friendly AFM available

- Open side access for faster sample and tip exchange
- Intuitive laser alignment with pre-aligned tip mount and unique on-axis, top down view
- Faster head removal with dovetail lock mount
- Easy to use interface with automatic settings

Versatile range of modes and options

- Comprehensive set of measurement modes and characterizations make this one of our most versatile AFMs
- Expanded capabilities with optional accessories and upgrades
- Advanced electrical measurements for failure analysis (FA)

Flat Orthogonal XY Scanning Without Scanner Bow

Park's Crosstalk Elimination removes scanner bow, allowing flat orthogonal XY scanning regardless of scan location, scan rate, and scan size. It shows no background curvature even on flattest samples, such as an optical flat, and with various scan offsets. This provides you with a very accurate height measurement and precision nanometrology for the most challenging problems in research and engineering.

Decoupled XY and Z Scanners

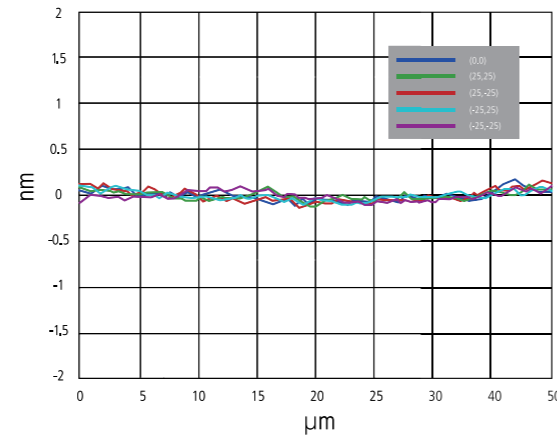
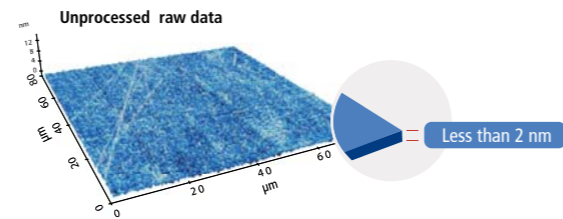
The fundamental difference between Park and its closest competitor is in the scanner architecture. Park's unique flexure based independent XY scanner and Z scanner design allows unmatched data accuracy in nano resolution in the industry.



Accurate Surface Measurement

"Flat" sample surface as it is!

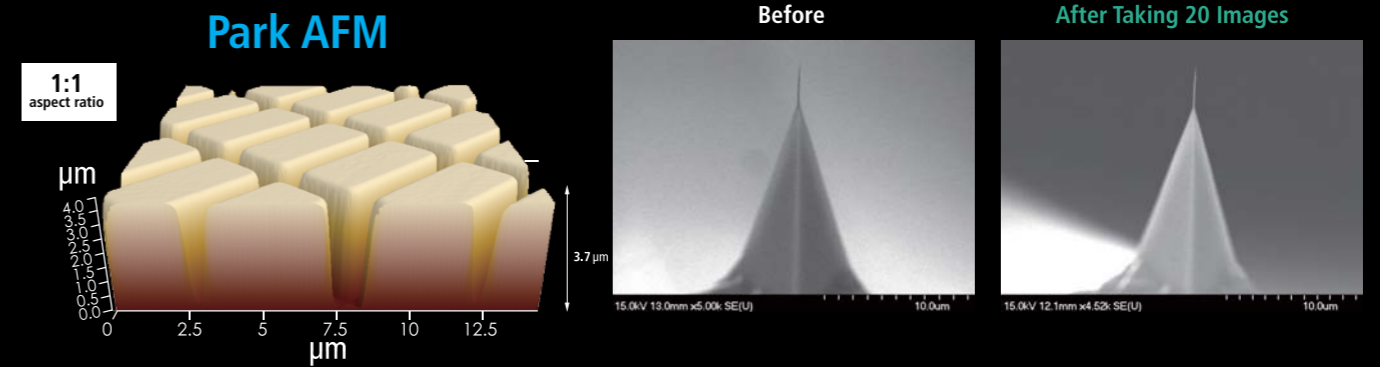
- Low residual bow
- No need for software processing (raw data)
- Accurate results independent of scan location



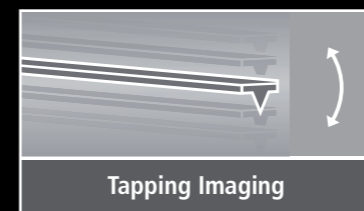
True Non-Contact™ Mode Preserves Tip Sharpness

AFM tips are so brittle that touching a sample will instantly reduce the resolution and quality of the image they produce. For soft and delicate samples, the tip will also damage the sample and result in inaccurate sample height measurements, something that can cost you valuable time and money.

True Non-Contact™ mode, a scan mode unique to Park AFMs, consistently produces high resolution and accurate data while maintaining the integrity of the sample.

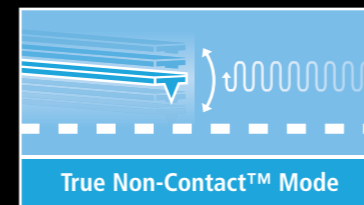


Accurate Feedback by Faster Z-servo enables True Non-Contact AFM



Tapping Imaging

- Quick tip wear = Blurred low-resolution scan
- Destructive tip-sample interaction = Sample damage and modification
- Highly parameter-dependent



True Non-Contact™ Mode

- Less tip wear = Prolonged high-resolution scan
- Non-destructive tip-sample interaction = Minimized sample modification
- Immunity from parameter dependent results

Park XE15

Equipped with the most innovative AFM technology

1 Flexure-Guided Scanner with 100 μm x 100 μm Scan Range

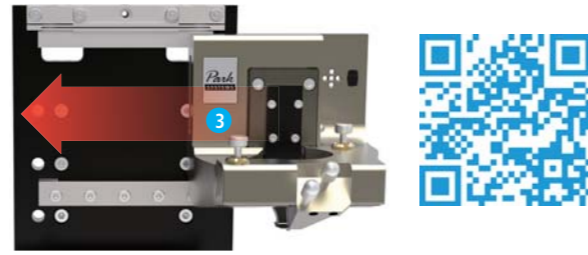
The XY scanner consists of symmetrical 2-dimensional flexure and high-force piezoelectric stacks provides high orthogonal movement with minimal out-of-plane motion as well as high responsiveness essential for precise sample scanning in the nanometer scale.

2 Flexure-Guided High Force Z Scanner

Driven by a high-force piezoelectric stack and guided by a flexure structure, its rigidity allows it to move at higher speeds in the vertical direction than the scanners used in conventional AFMs. The maximum Z scan range can be extended from 12 μm to 25 μm with the optional long range Z scanner (optional).

3 Slide-to-Connect SLD Head

The AFM head is easily inserted or removed by sliding it along a dovetail rail. The low coherency of the Super Luminescence Diode (SLD) enables accurate imaging of highly reflective surfaces and precise measurements for pico-Newton Force-distance spectroscopy. The SLD wavelength eliminates interference issues for users interested in combining the AFM with experiments in the visible spectrum.

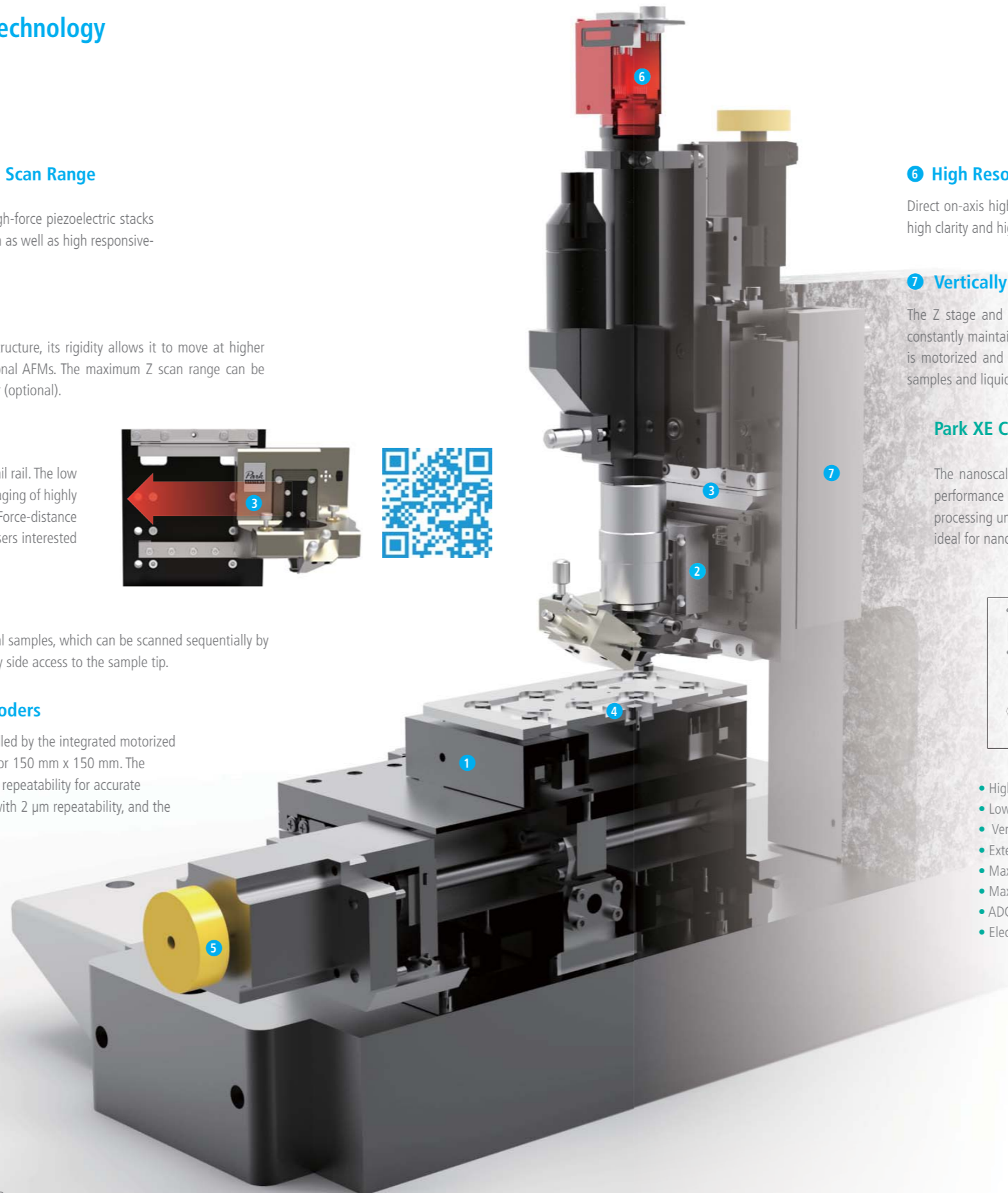


4 Multi-sample Chuck

The specially designed multi-sample chuck can load up to 16 individual samples, which can be scanned sequentially by MultiSample Scan Automation. The unique head design allows for easy side access to the sample tip.

5 Motorized XY Sample Stage with Optional Encoders

The measurement location of the sample is easily and precisely controlled by the integrated motorized XY stage. The travel range of the XY sample stage can be configured for 150 mm x 150 mm. The encoders, if used with the motorized stages, enable higher positioning repeatability for accurate sample positioning. The encoded XY stage travels in 1 μm resolution with 2 μm repeatability, and the encoded Z stage, in 0.1 μm resolution with 1 μm repeatability.



6 High Resolution Digital CCD Camera with Digital Zoom

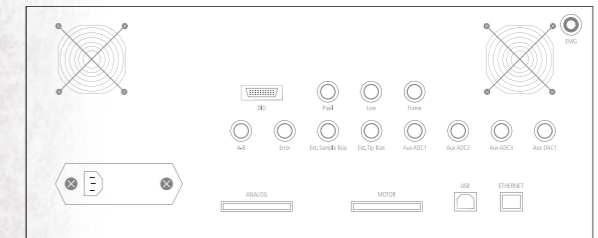
Direct on-axis high resolution digital CCD camera with digital zoom capability allows high clarity and high resolution image quality regardless of panning.

7 Vertically Aligned Motorized Z Stage and Focus Stage

The Z stage and focus stage engage the cantilever with the sample surface while constantly maintaining a clear field of vision for the user. And because the focus stage is motorized and software controlled, it has the precision necessary for transparent samples and liquid cell applications.

Park XE Control Electronics with DSP Board in Controller

The nanoscale signals from the AFM are controlled and processed by the high performance Park XE electronics. With its low noise design and high speed processing unit, Park XE electronics successfully realize True Non-Contact™ mode ideal for nanoscale imaging as well as precise voltage and current measurement.



- High performance processing unit of 600 MHz and 4800 MIPS speed
- Low noise design for precise voltage and current measurement
- Versatile system to utilize various SPM techniques
- External Signal Access Module to access AFM input/output signals
- Maximum 16 data images
- Maximum data size: 4096 x 4096 pixels
- ADC/DAC in 16 bit, 500 kHz speed
- Electric noise isolation from PC by TCP/IP connection

Park XE15

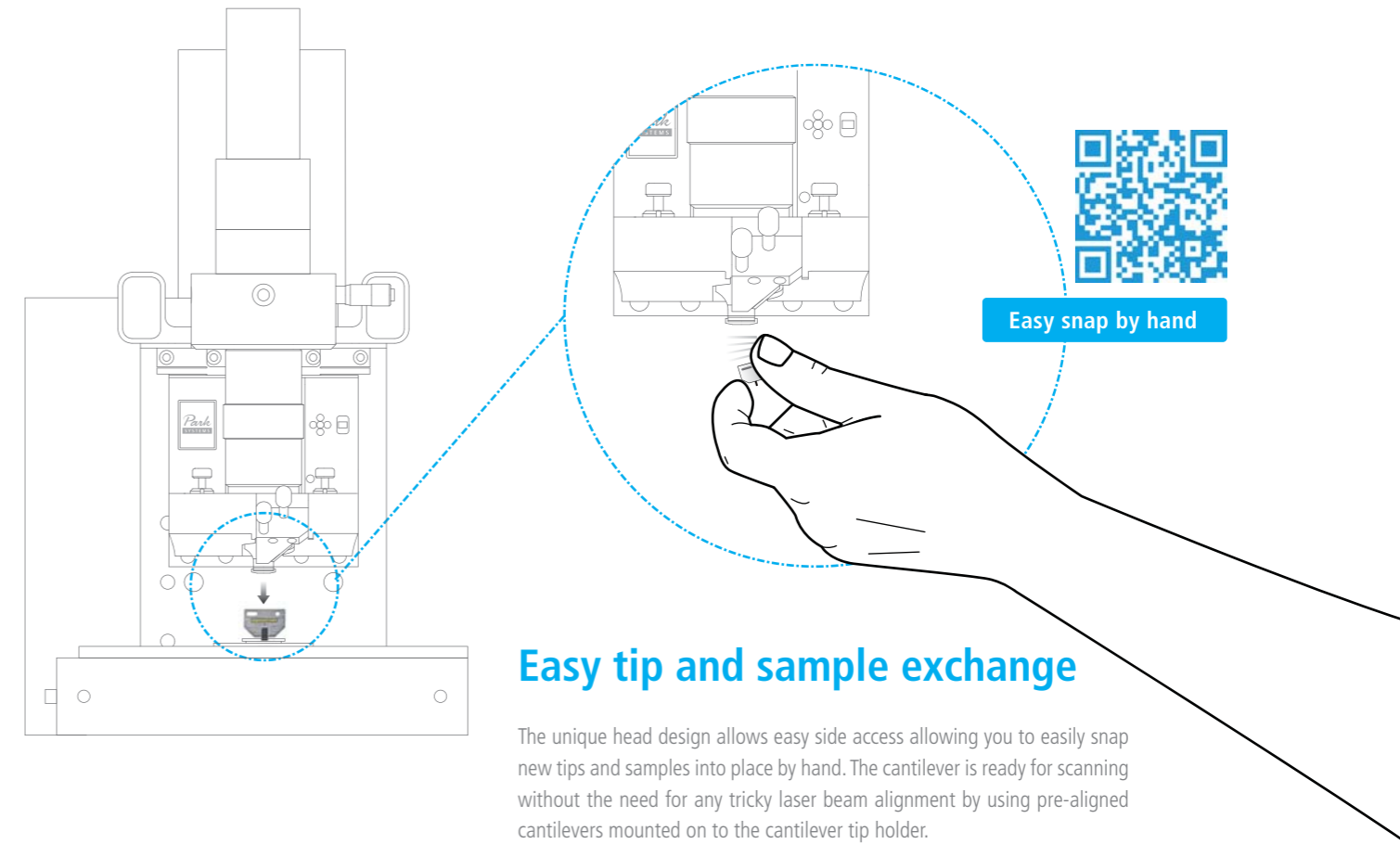
Why the most affordable AFM is also accurate and easy to use

MultiSample™ scan

Using the motorized sample stage, MultiSample Scan™ enables programmable multiple region imaging in step-and-scan automation. Here's how it works:

- 1 Register multiple scan positions defined by a user
- 2 Image from the first scan position
- 3 Lift a cantilever
- 4 Move the motorized stage to the next user defined coordinate
- 5 Approach
- 6 Repeat scan

The registration of multiple scan positions are easily carried out by either entering sample-stage coordinates or sample de-skewing by two reference points. This automated feature greatly increases productivity by reducing the need for your interaction during the scan process.



Easy tip and sample exchange

The unique head design allows easy side access allowing you to easily snap new tips and samples into place by hand. The cantilever is ready for scanning without the need for any tricky laser beam alignment by using pre-aligned cantilevers mounted on to the cantilever tip holder.

Direct on-axis optics

The intuitive direct on-axis sample view from the top allows you to navigate the sample surface easily to find the target area. A high-resolution digital camera with zoom capability allows clarity and great image quality regardless of panning motion.

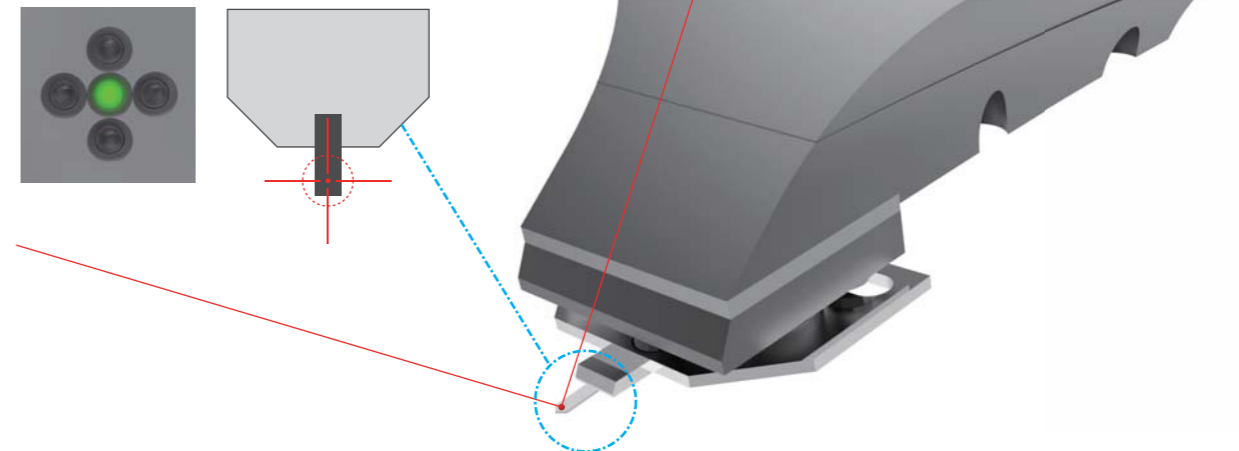


Easy, intuitive laser beam alignment

With our advanced pre-aligned cantilever holder, the **laser beam** is focused on the cantilever upon placement. Furthermore, the natural on-axis, top-down view—the only one in the industry—allows you to easily find the laser spot. Since the laser beam falls vertically onto the cantilever, you can intuitively move the laser spot along the X- and Y-axis by rotating two positioning knobs. As a result, you can easily find the laser and position it onto the position-sensitive photodiode using our operation software's beam alignment user interface. From there, all you will need is a minor adjustment to maximize the signal prior to starting data acquisition.



laser beam is always focused on the cantilever upon replacement



Park XE15

Specification

Scanner	XY scanner Single-module flexure XY scanner with closed-loop control Scan range: 100 μm × 100 μm	Z scanner Guided high-force Z scanner Scan range: 12 μm 25 μm (optional)	Stage XY travel range: 150 mm × 150 mm Z travel range: 27.5 mm, optional precision encoders for better stage repeatability Focus travel range: 20 mm (motorized), optional precision encoders for repeatable XY positioning		
Vision	Sample Mount Direct on-axis vision of sample surface and cantilever Coupled with 10× objective lens (20× optional) Field-of-view: 480 μm × 360 μm (with 10× objective lens) Camera: 1 M Pixel 5 M Pixel (optional)		Sample size: Up to 200 mm Thickness: Up to 20 mm	Software XEP Dedicated system control and data acquisition software Adjusting feedback parameters in real time Script-level control through external programs (optional)	XEI AFM data analysis software (running on Windows, MacOS X, and Linux)
Electronics	Dimensions in mm High performance DSP: 600 MHz with 4800 MIPS Maximum 16 data images Maximum data size: 4096 × 4096 pixels Signal inputs: 20 channels of 16 bit ADC at 500 kHz sampling Signal outputs: 21 channels of 16 bit DAC at 500 kHz settling Synchronous signal: End-of-image, end-of-line, and end-of-pixel TTL signals		Active Q control (optional) Cantilever spring constant calibration (optional) CE Compliant Power: 120 W Signal Access Module (Optional)		
Options/Modes	Standard Imaging <ul style="list-style-type: none"> • True Non-Contact AFM • Basic Contact AFM • Lateral Force Microscopy (LFM) • Phase Imaging • Intermittent (tapping) AFM 	Chemical Properties <ul style="list-style-type: none"> • Chemical Force Microscopy with Functionalized Tip • Electrochemical Microscopy (EC-STM and EC-AFM) 	Dielectric/Piezoelectric Properties <ul style="list-style-type: none"> • Electric Force Microscopy (EFM) • Dynamic Contact EFM (DC-EFM) • Piezoelectric Force Microscopy (PFM) • PFM with High Voltage 		
Force Measurement <ul style="list-style-type: none"> • Force Distance (F-D) Spectroscopy • Force Volume Imaging 	Magnetic Properties <ul style="list-style-type: none"> • Magnetic Force Microscopy (MFM) 	Optical Properties <ul style="list-style-type: none"> • Tip-Enhanced Raman Spectroscopy (TERS) • Time-Resolved Photo Current Mapping (Tr-PCM) 			
Electrical Properties <ul style="list-style-type: none"> • Conductive AFM • I-V Spectroscopy • Scanning Kelvin Probe Microscopy (SKPM/KPM) • SKPM with High Voltage • Scanning Capacitance Microscopy (SCM) • Scanning Spreading-Resistance Microscopy (SSRM) • Scanning Tunneling Microscopy (STM) • Time-Resolved Photo Current Mapping (Tr-PCM) 	Mechanical Properties <ul style="list-style-type: none"> • Force Modulation Microscopy (FMM) • Nanoindentation • Nanolithography • Nanolithography with High Voltage • Nanomanipulation • Piezoelectric Force Microscopy (PFM) 	Thermal Properties <ul style="list-style-type: none"> • Scanning Thermal Microscopy (SThM) 			
Accessories <ul style="list-style-type: none"> • Electrochemistry Cell • Universal Liquid Cell with Temperature Control • Sample Stages with Temperature Control • Magnetic Field Generator 					

Park XE15

Power for any project

With a wide range of scanning modes and modular design, the Park XE15 has the power and flexibility you need for any project.

Surface Roughness Measurement

- True Non-Contact Mode
- Dynamic Force Mode

Electrical Characterization

- Conductive AFM (ULCA and VECA)
- Electric Force Microscopy (EFM)
- Piezoelectric Force Microscopy (PFM)
- Scanning Capacitance Microscopy (SCM)
- Scanning Kelvin Probe Microscopy (SKPM)
- Scanning Spreading Resistance Microscopy (SSRM)
- Scanning Tunneling Microscopy (STM)
- Time-Resolved Photo Current Mapping (Tr-PCM)

Thermal Characterization

- Scanning Thermal Microscopy (SThM)

Mechanical Characterization

- Force Modulation Microscopy (FMM)
- Force-Distance (F-d) Spectroscopy
- Force Volume Imaging
- Lateral Force Microscopy (LFM)
- Nanoindentation
- Nanolithography
- Phase Imaging

Magnetic Characterization

- Magnetic Force Microscopy (MFM)

Options



Active Temperature-controlled Acoustic Enclosure

- Innovative control brings the system quickly to its temperature equilibrium
- Temperature stability of less than 0.05 °C within 10 minutes of closing AE door
- Includes an active vibration isolation system



Encoders for Motorized Stage

- The encoded XY stage travels in 1 μm resolution with 2 μm repeatability.
- The encoded Z stage travels in 0.1 μm resolution with 1 μm repeatability.



Sample Plates

- Vacuum grooves to hold wafers
- Sample dimension: Up to 150 mm



25 μm Z-scanner Head

- Z scan range: 25 μm
- Resonant frequency: 1.7 kHz
- Laser type: LD (650 nm) or SLD (830 nm)
- Noise floor: 0.03 nm (typical), 0.05 nm (maximum)



XE Optical Head

- Optical access: top and side
- Z scan range: 12 μm or 25 μm
- Laser type: LD (650 nm) or SLD (830 nm)
- Noise floor: 0.03 nm (typical), 0.05 nm (maximum)
- Resonant frequency: 3 kHz (12 μm XE Head), 1.7 kHz (25 μm XE Head)



Clip-type Probehead

- Unmounted cantilever can be used
- Tip bias range: -10 V to + 10 V
- Tip bias function available for EFM and Conductive AFM
- Support all the standard and advanced modes but STM, SCM, and in-liquid imaging



Signal Access Module (SAM)

- Enables access to various input/output signals for AFM
- Scanner driving signal for the XY and Z scanners
- Position signal for the XY and Z scanners
- Cantilever deflection signals of the vertical/lateral direction
- Bias signal for the sample and the cantilever
- Driving signal for XE15
- Auxiliary input signal to the system

High Resolution Imaging

Si (100) Epi wafer



Topography by True Non-Contact™ Mode (1 μm x 1 μm)

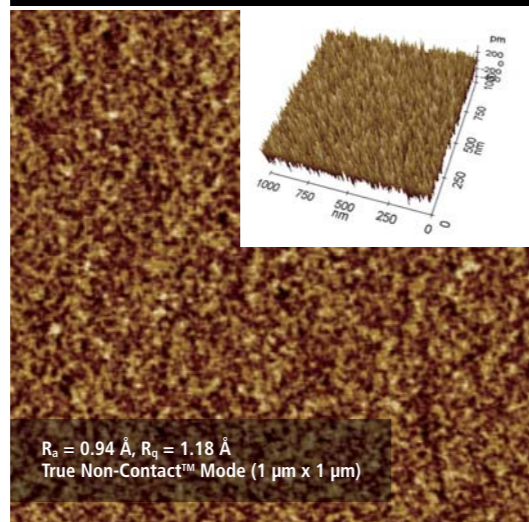
ZnO fibers with polylactic acid



Topography by True Non-Contact™ Mode (15 μm x 15 μm)

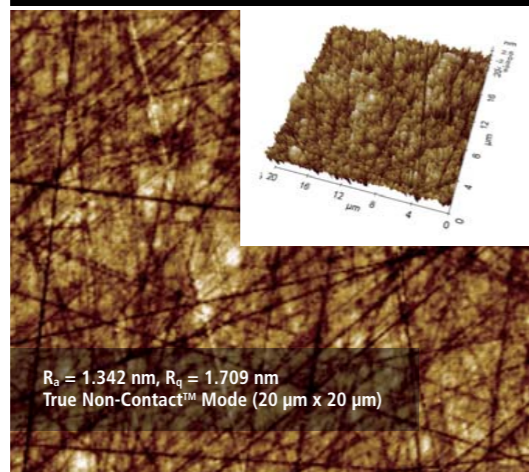
Surface Roughness Measurement

Si wafer



$R_a = 0.94 \text{ \AA}$, $R_q = 1.18 \text{ \AA}$
True Non-Contact™ Mode (1 μm x 1 μm)

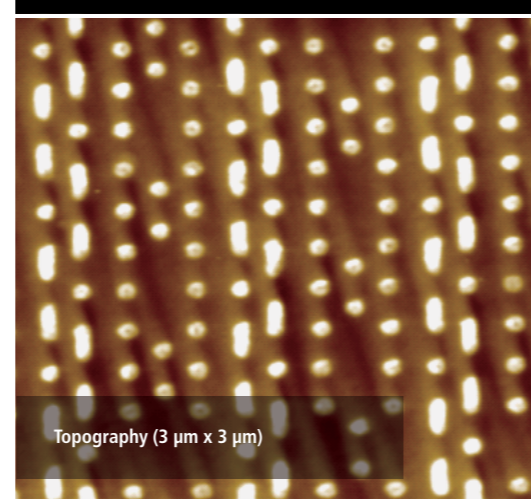
SiC substrate



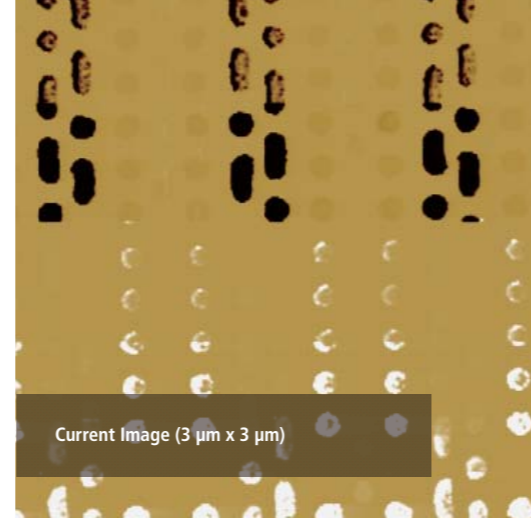
$R_a = 1.342 \text{ nm}$, $R_q = 1.709 \text{ nm}$
True Non-Contact™ Mode (20 μm x 20 μm)

Electrical Characterization

Conductive AFM
Current change according to sample bias



Topography (3 μm x 3 μm)



Current Image (3 μm x 3 μm)

XE-Heads	12 μm XE-Head	25 μm XE-Head	XE Optical Head	Hysitron Triboscope Adaptor Head
Probeheads	Clip-type Probehead	Liquid Probeheads (open/closed)	SCM Probehead	STM Probehead
Liquid Cells	Universal Liquid Cell	Open Liquid Cell	Electrochemistry Cell	
Environmental Control	Heating & Cooling Stage	Heating Stage		
Accessories	Signal Access Module	Q Controller	Vacuum Chuck	Non-magnetic Sample Holder
	Cross-sectional Sample Holder	High Voltage Toolkit		